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SEMICONDUCTOR

NEPP
The Changing Tide

June 15, 2016

GSFC

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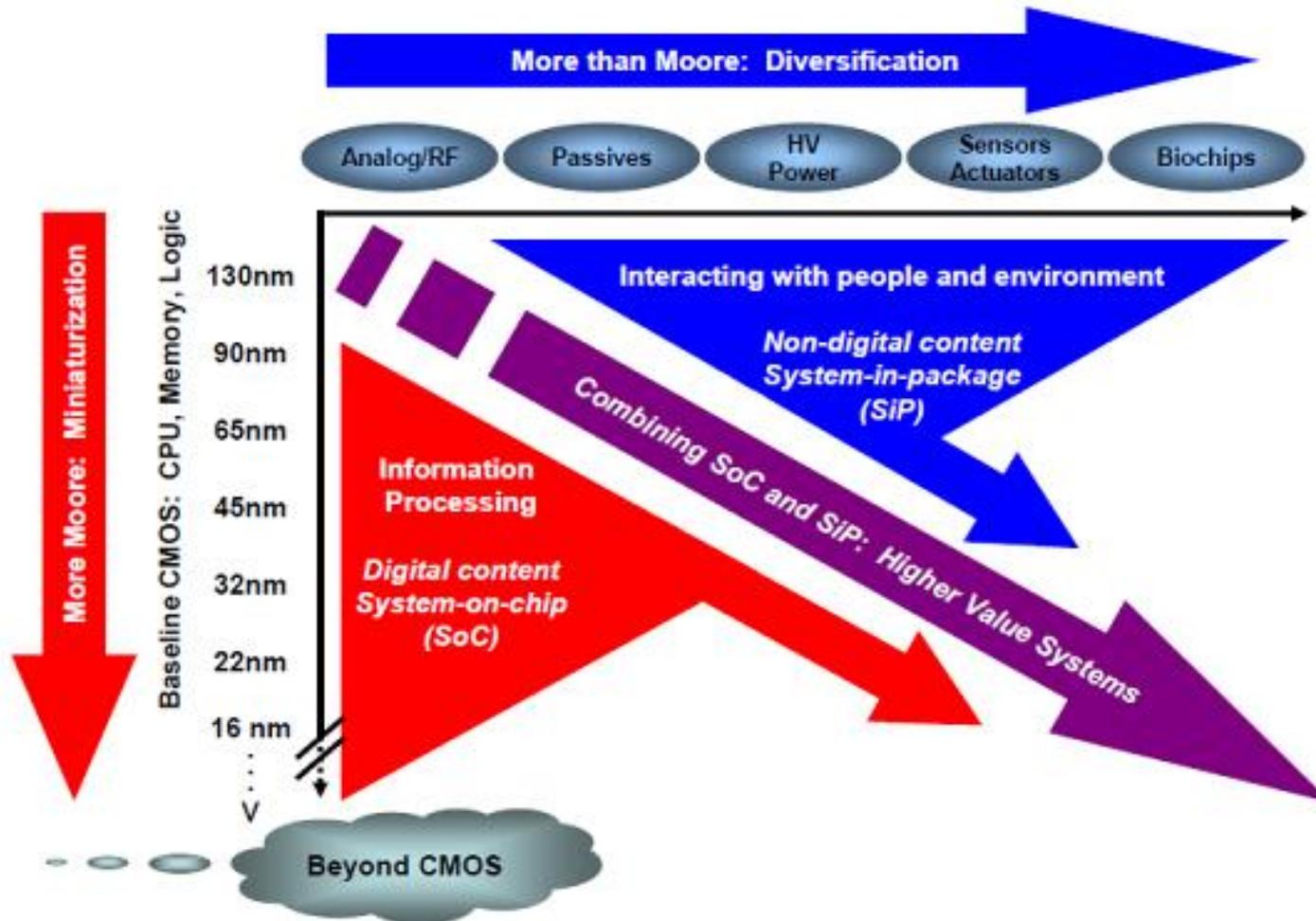


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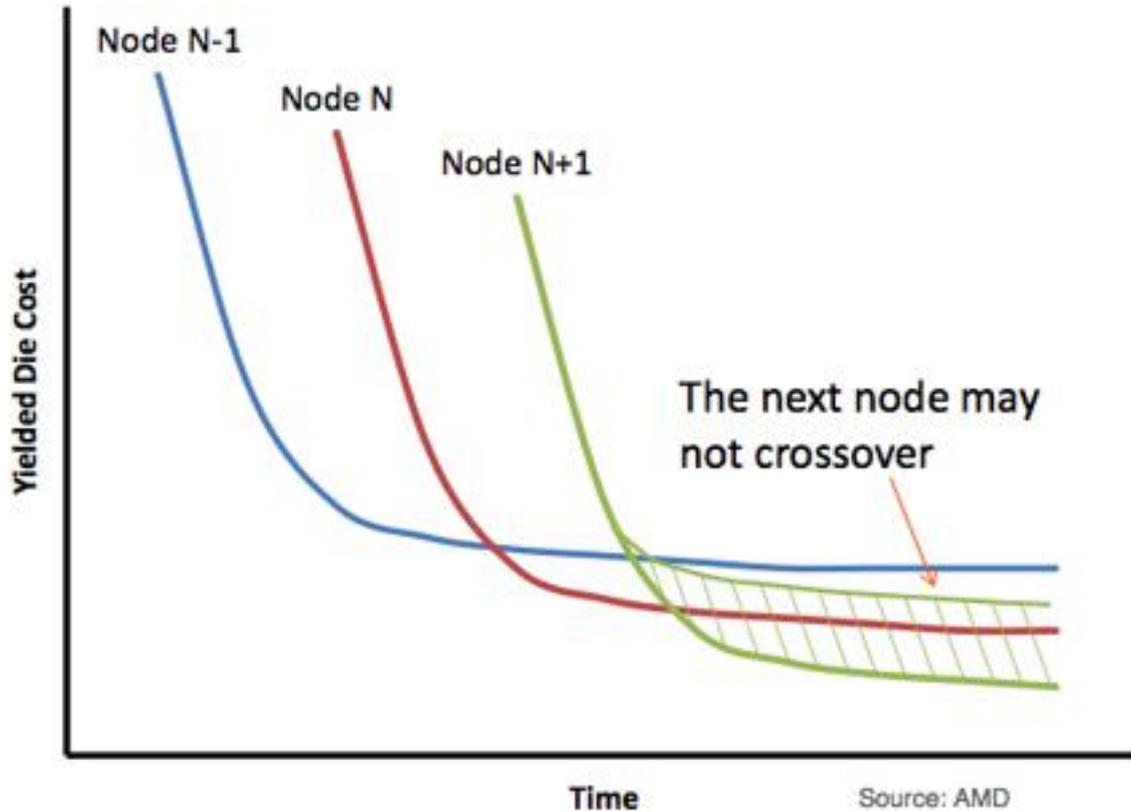
MOORE'S LAW



Moore's Law & More than Moore (MtM)

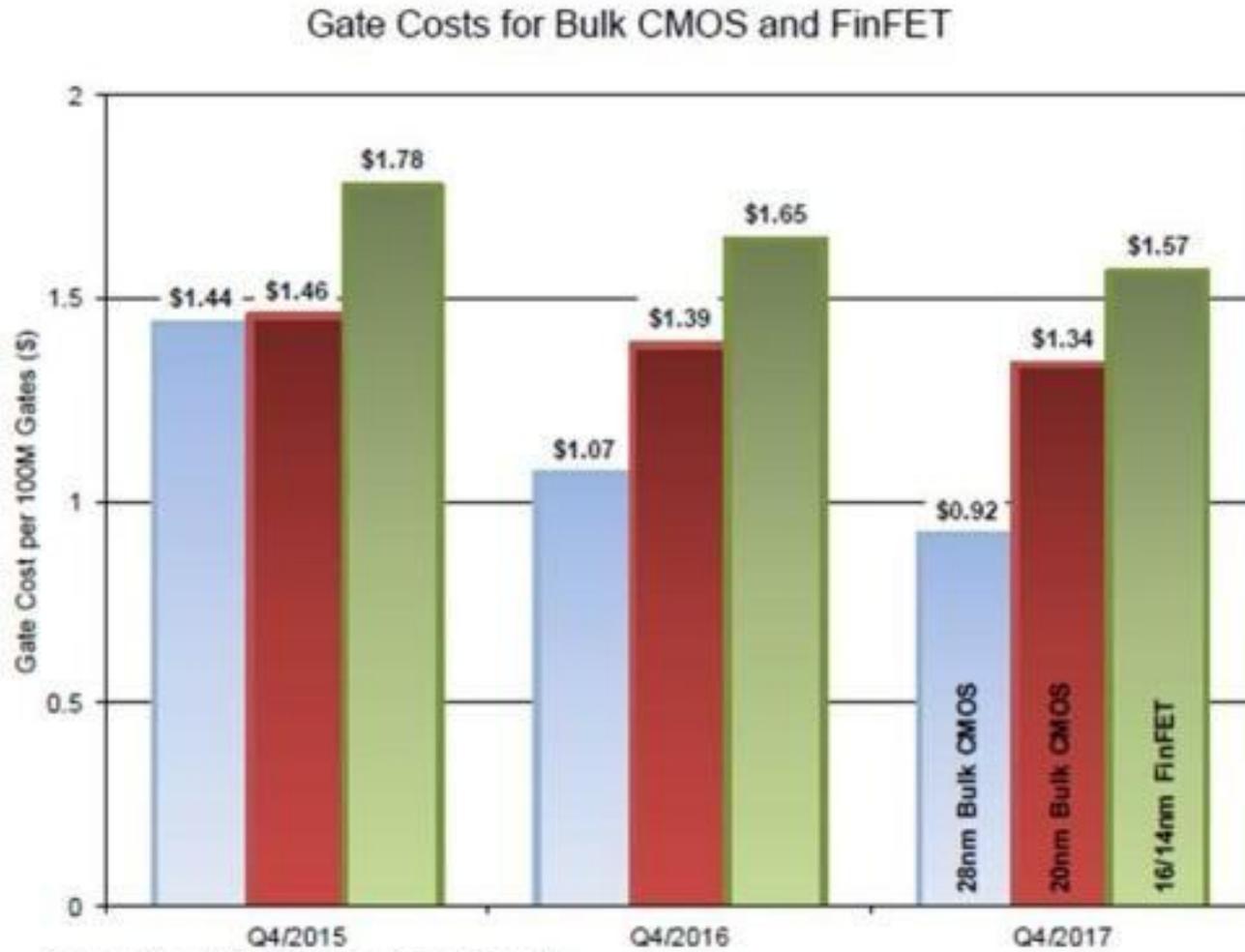


Expiring Economics



AMD 2014 3D-ASIP

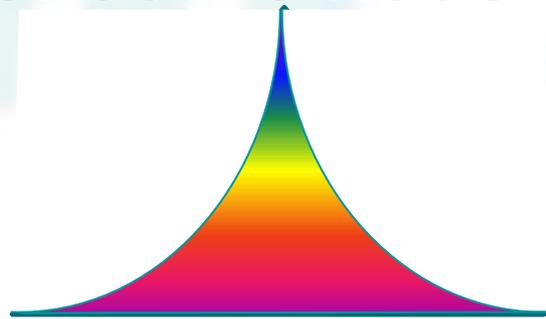
Cost Trend Reversal



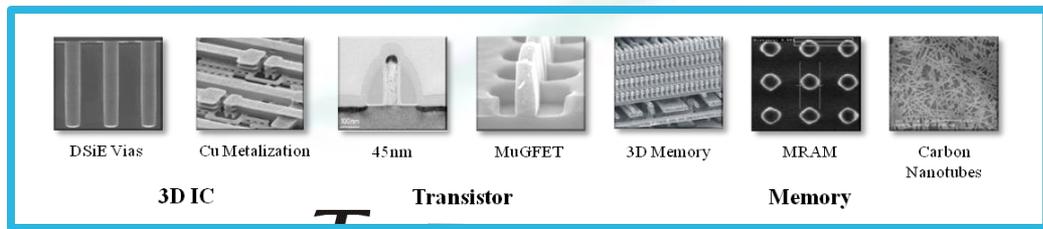
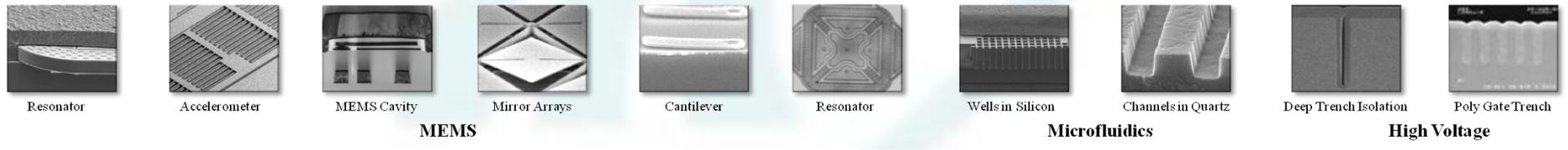
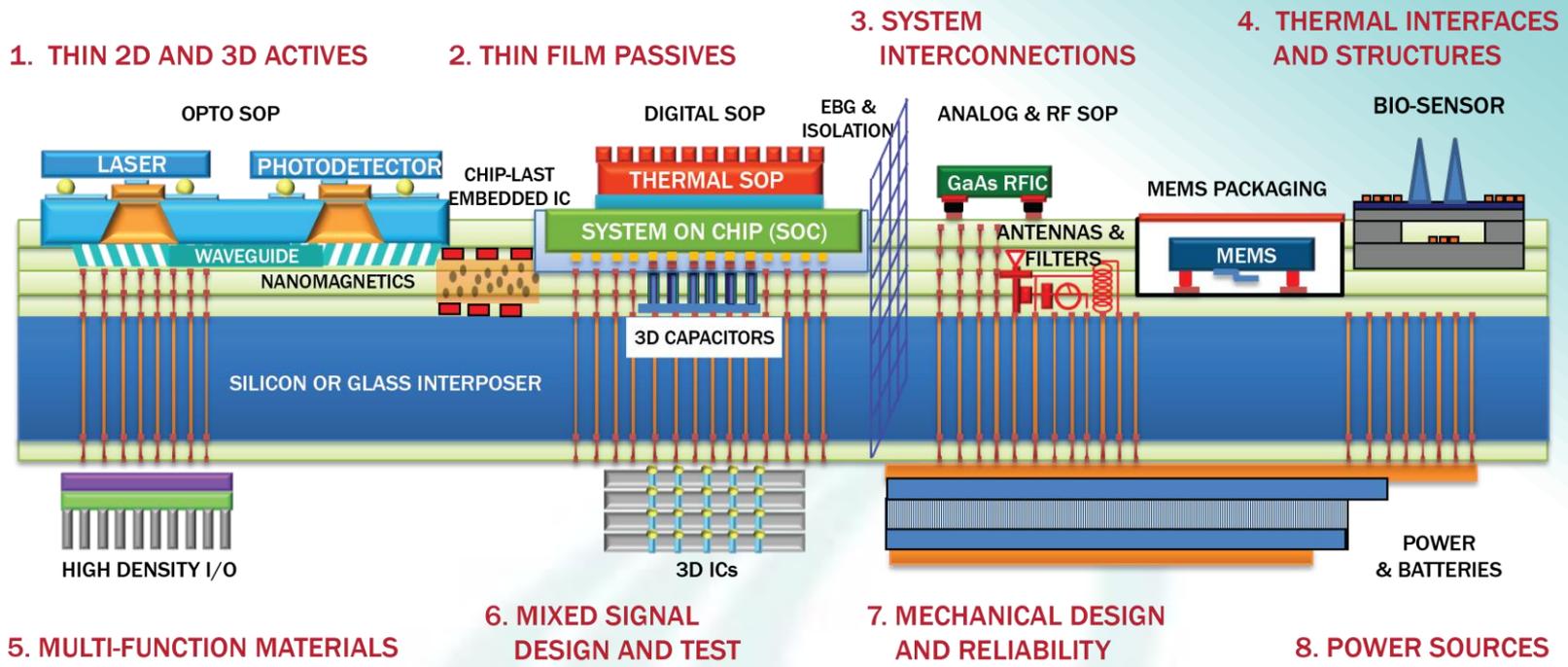
Source: International Business Strategies, Inc.

More Moore

- The end is near...
 - 16nm, 14nm, 10nm, 8nm, 6nm, 5nm ...
 - Maybe its now. Maybe it's in 3 years or 5 years, but the end of scaling is going to happen within the next decade
- Most cost effective node for years...28nm?



More Than Moore

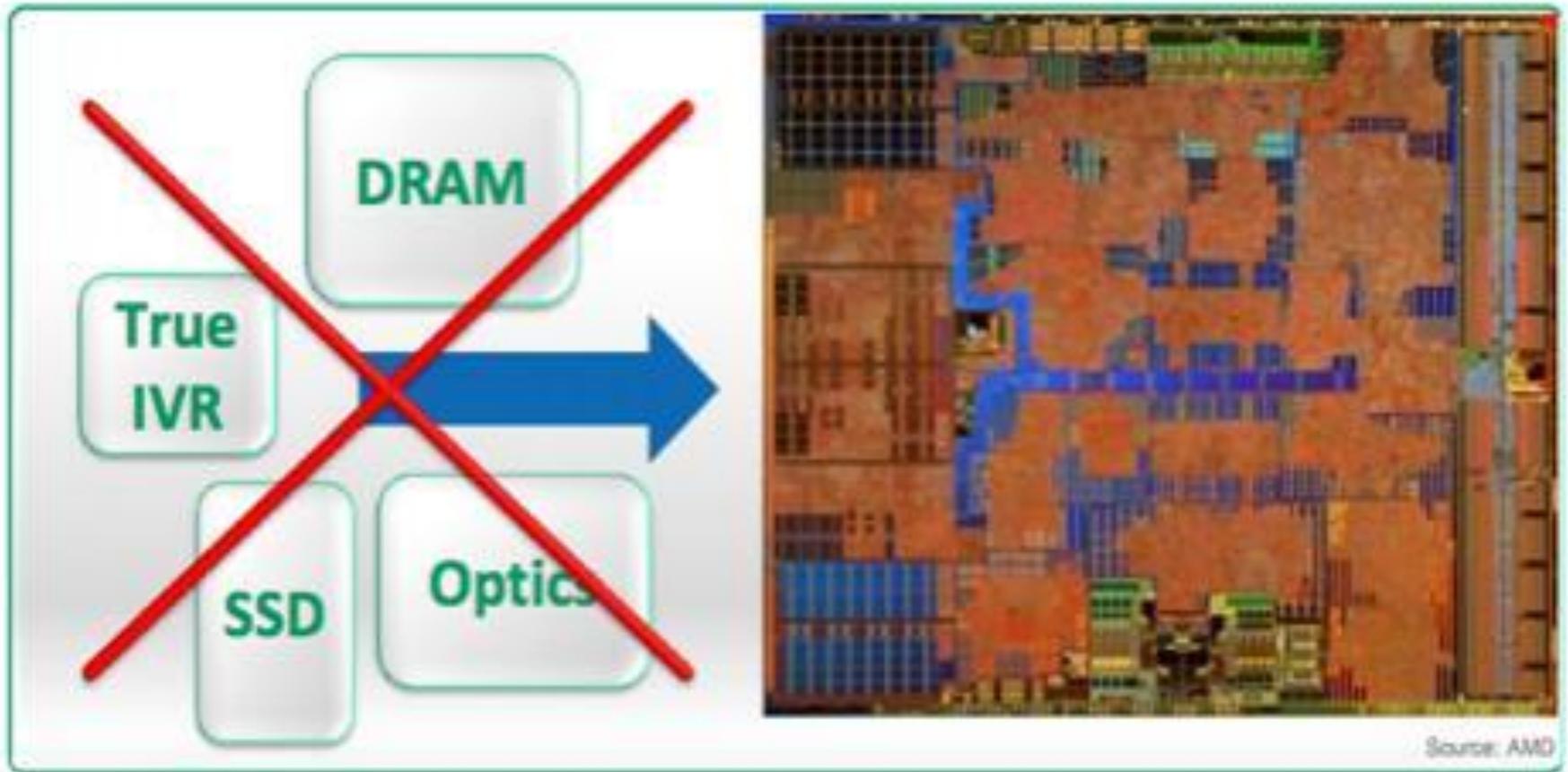




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WHAT ARE THE DRIVERS OF CHANGE?

The Apples & Oranges of SOC



AMD 2014 3D-ASIP

Internet Of Things



ImpactLab.net



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MORE THAN MOORE

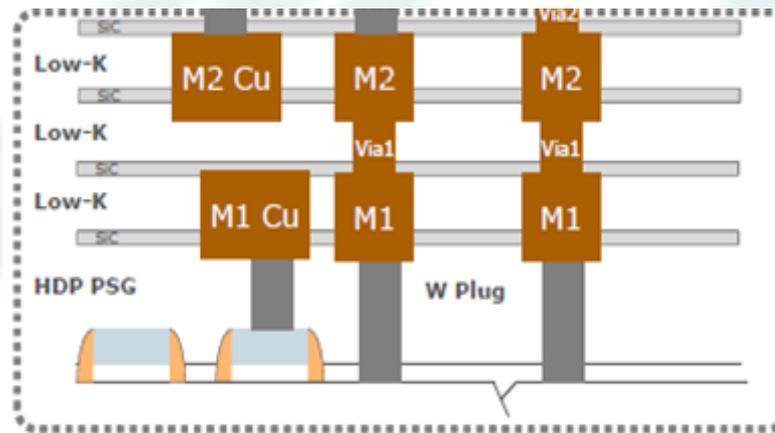
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The Fabrication Road to More Than Moore

Memories, CMOS, Photonics, III-V,
Novel Materials, Microfluidics, MEMS,
etc.

Build novel
structures BEOL

Start with FEOL
CMOS wafer



Integration Paths: Additive Silicon and 2.5/3D

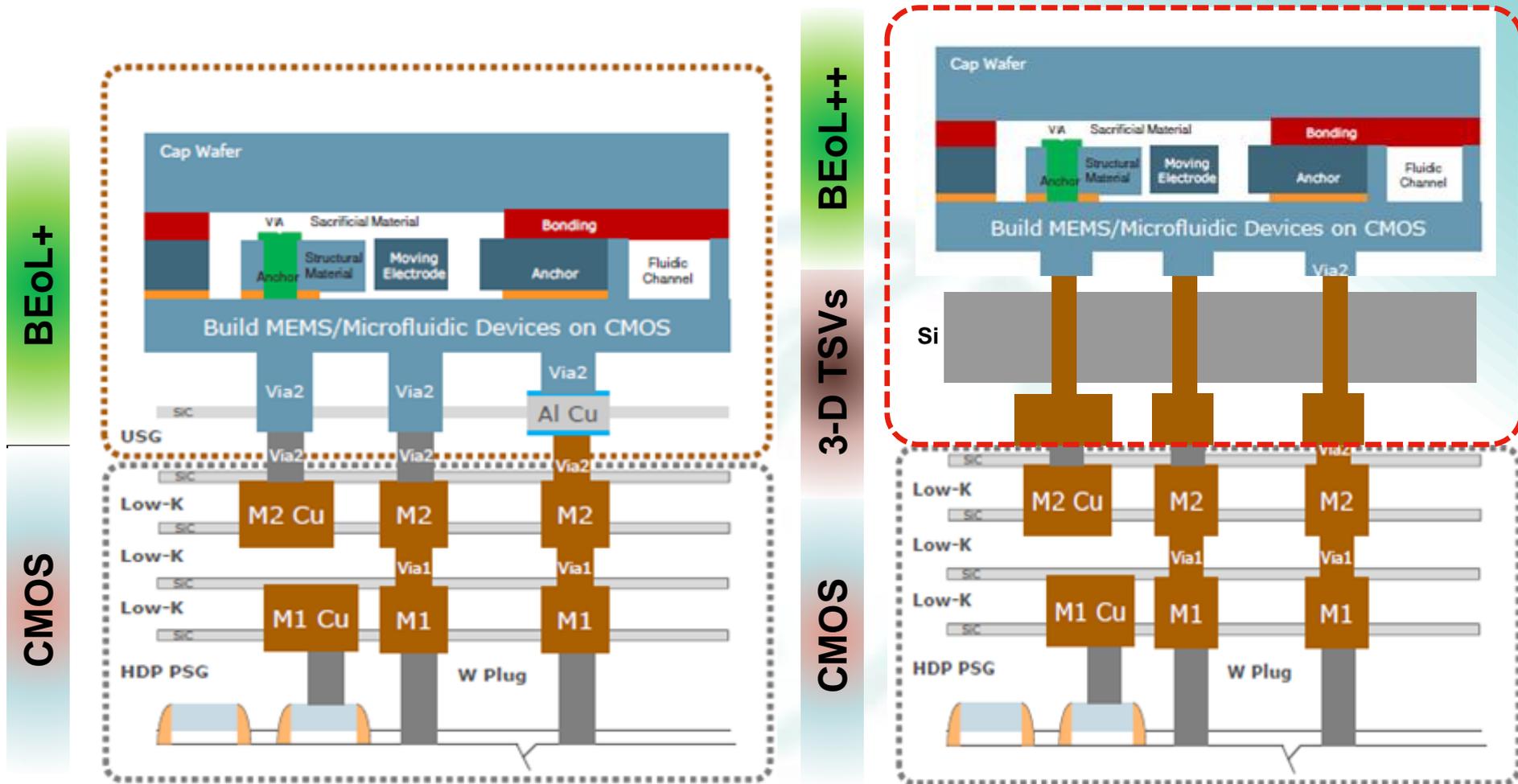
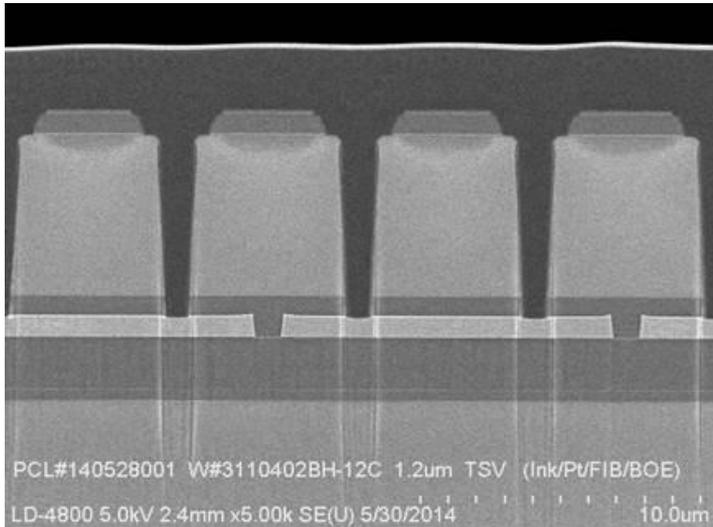
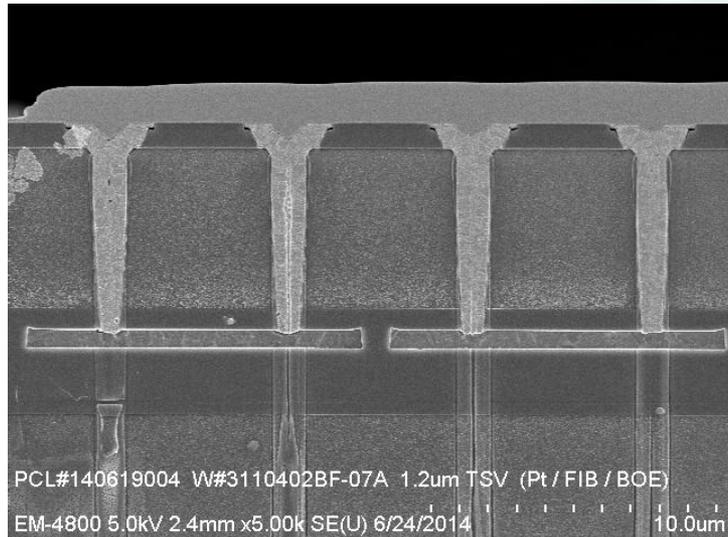


Figure 1: Non-digital devices built directly on CMOS (left), or built separately and joined through 3-D TSVs

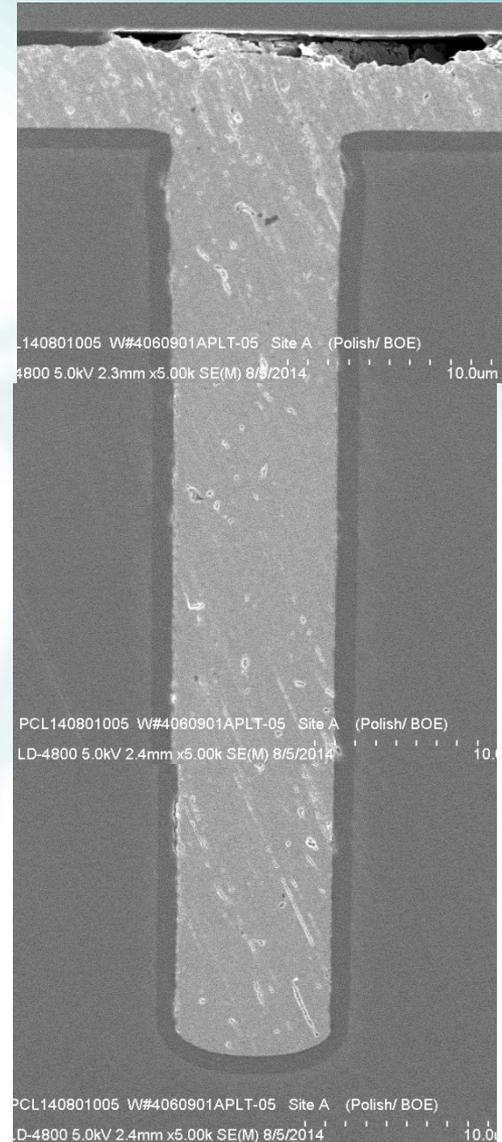
TSV Insertion to Create 2.5/3D Assemblies



1.2x6um
Tungsten
←



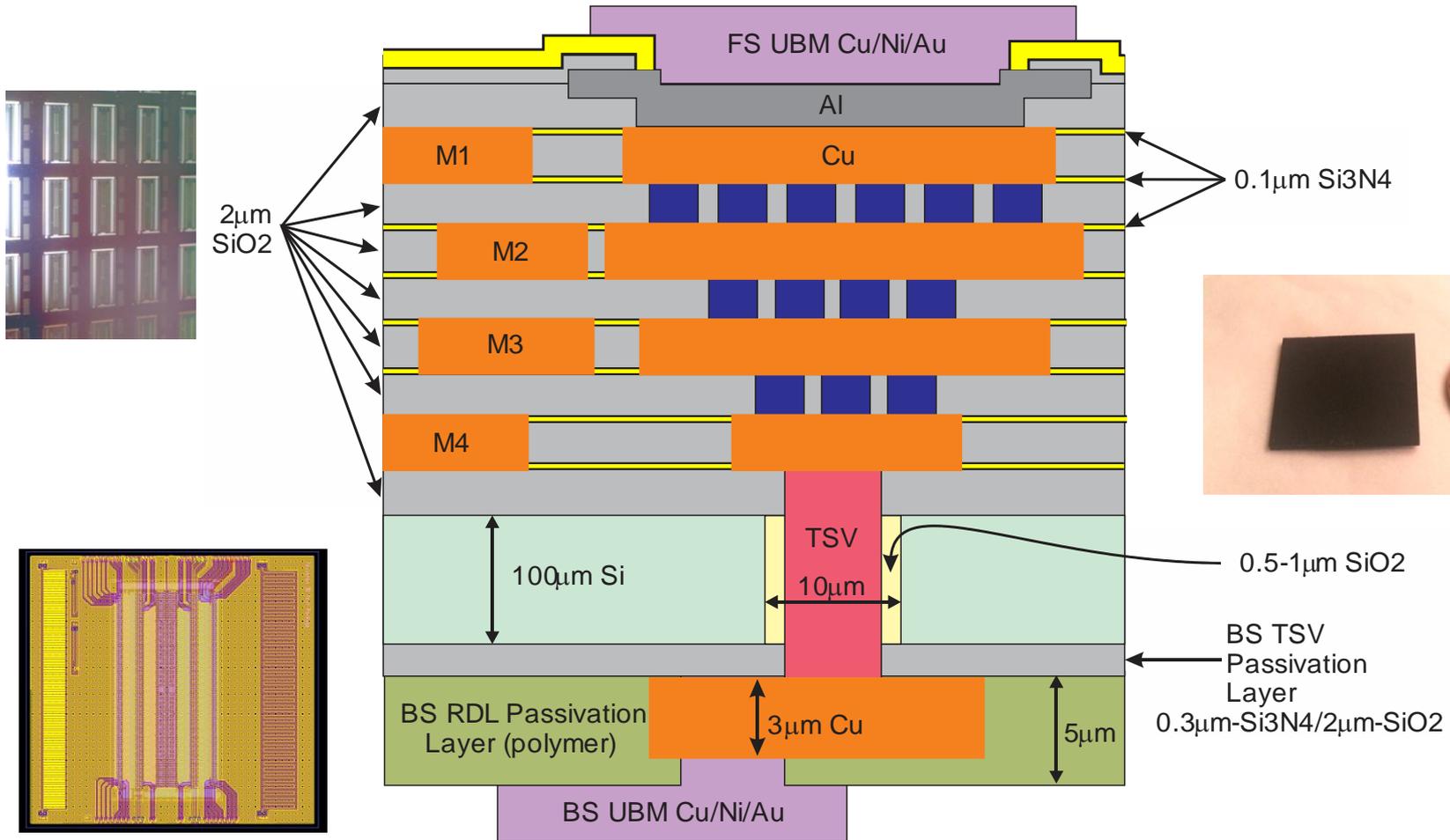
10x100um
Copper
→



New Elements Introduced to Fabrication

Typical CMOS Fab										Additional at Novati									
H																			He
Li	Be											B	C	N	O	F		Ne	
Na	Mg											Al	Si	P	S	Cl		Ar	
K	Ca	Sc	Ti	V	Cr	Mn	Fe	Co	Ni	Cu	Zn	Ga	Ge	As	Se	Br		Kr	
Rb	Sr	Y	Zr	Nb	Mo	Tc	Ru	Rh	Pd	Ag	Cd	In	Sn	Sb	Te	I		Xe	
Cs	Ba	La	Hf	Ta	W	Re	Os	Ir	Pt	Au	Hg	Tl	Pb	Bi	Po	At		Rn	
Fr	Ra	Ac	Rf	Db	Sg	Bh	Hs	Mt											
		Ce	Pr	Nd	Pm	Sm	Eu	Gd	Tb	Dy	Ho	Er	Tm	Yb	Lu				
		Th	Pa	U	Np	Pu	Am	Cm	Bk	Cf	Es	Fm	Md	No	Lr				

Si Interposers



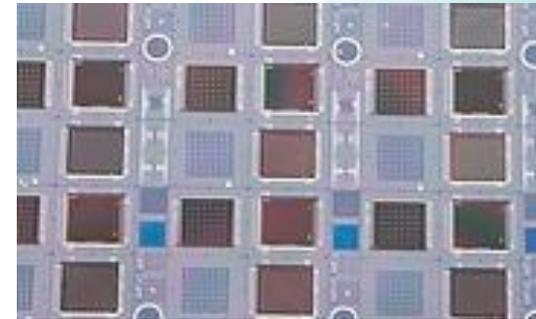
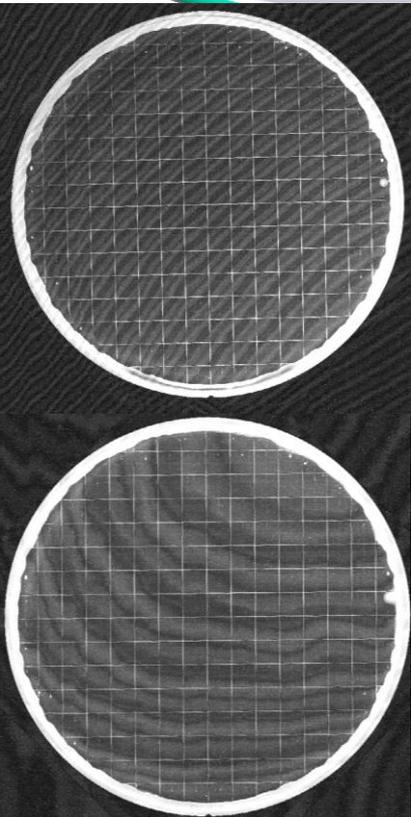
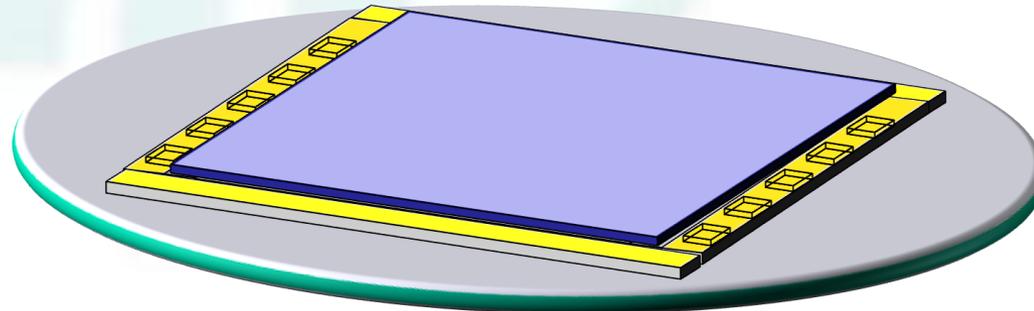
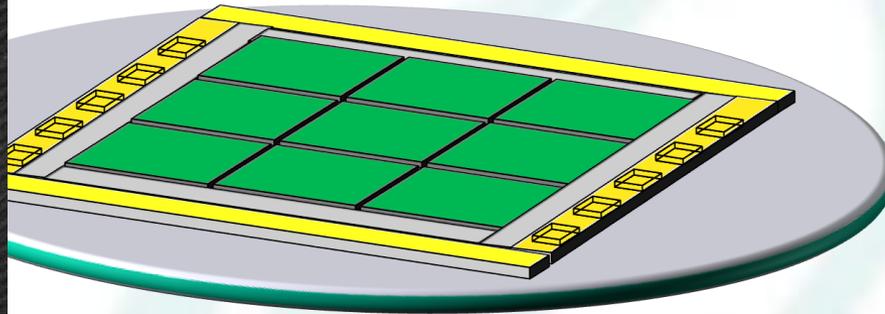
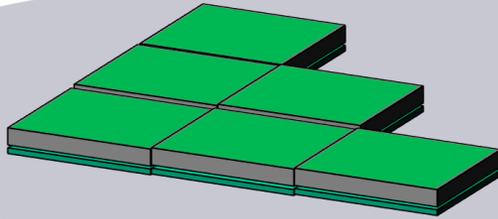
Interposer Parameters

Layer	Metal thickness	R(mΩ/□) at DC	W	L	Cg (fF)
M1	2μm	9.2	10	2	2.94
			200	10	58
M2	2μm	9.2	10	2	1.83
			200	10	21.0
M3	2μm	9.2	10	2	1.4
			200	10	19.7
M4	2μm	9.2	10	2	0.919
			200	10	13.9

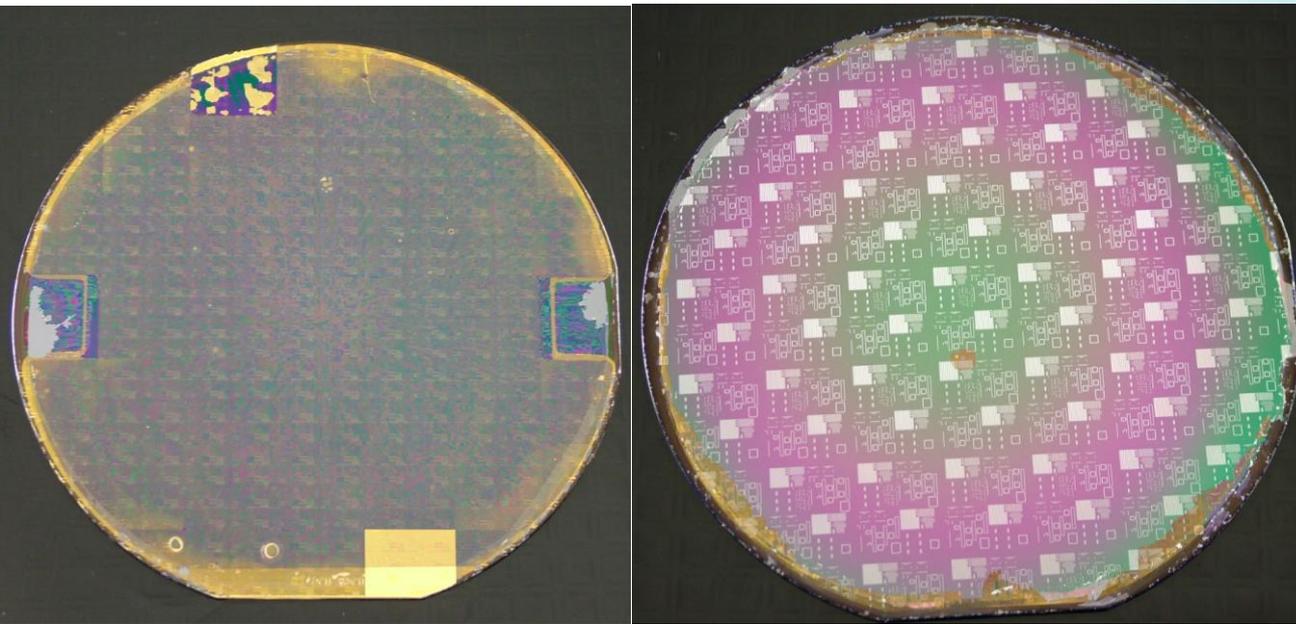
	TSV Diameter	TSV Height	Resistance	Cg (fF)
Filled	10μm	100μm	21.2mΩ	180
Conformal	80μm	300μm	~15mΩ	~600

Die on Wafer and Wafer-scale FPA

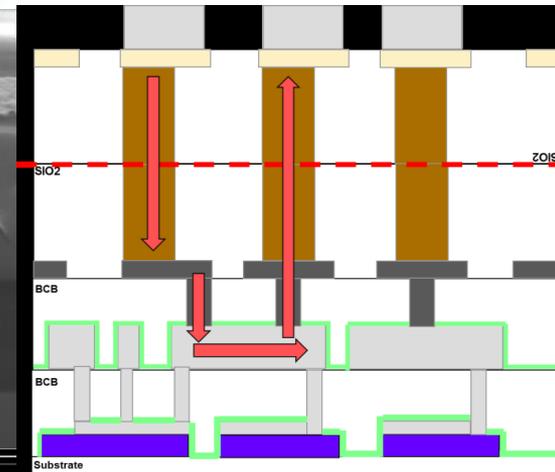
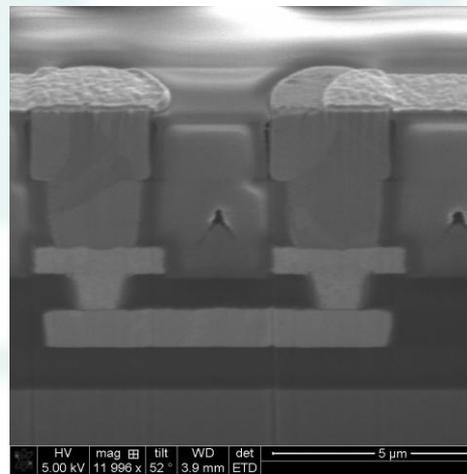
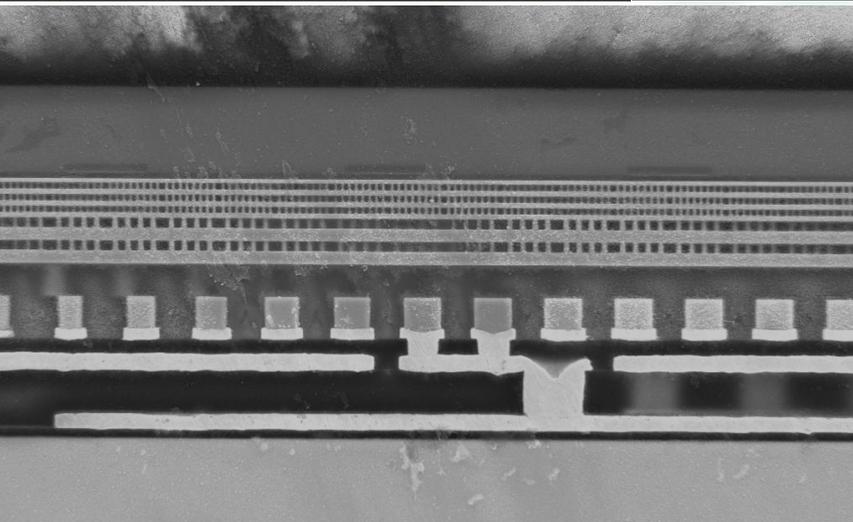
- Waferscale integration
- Up to 85 die assembly
- 10um die space
- 2um placement
- 150/200/300mm

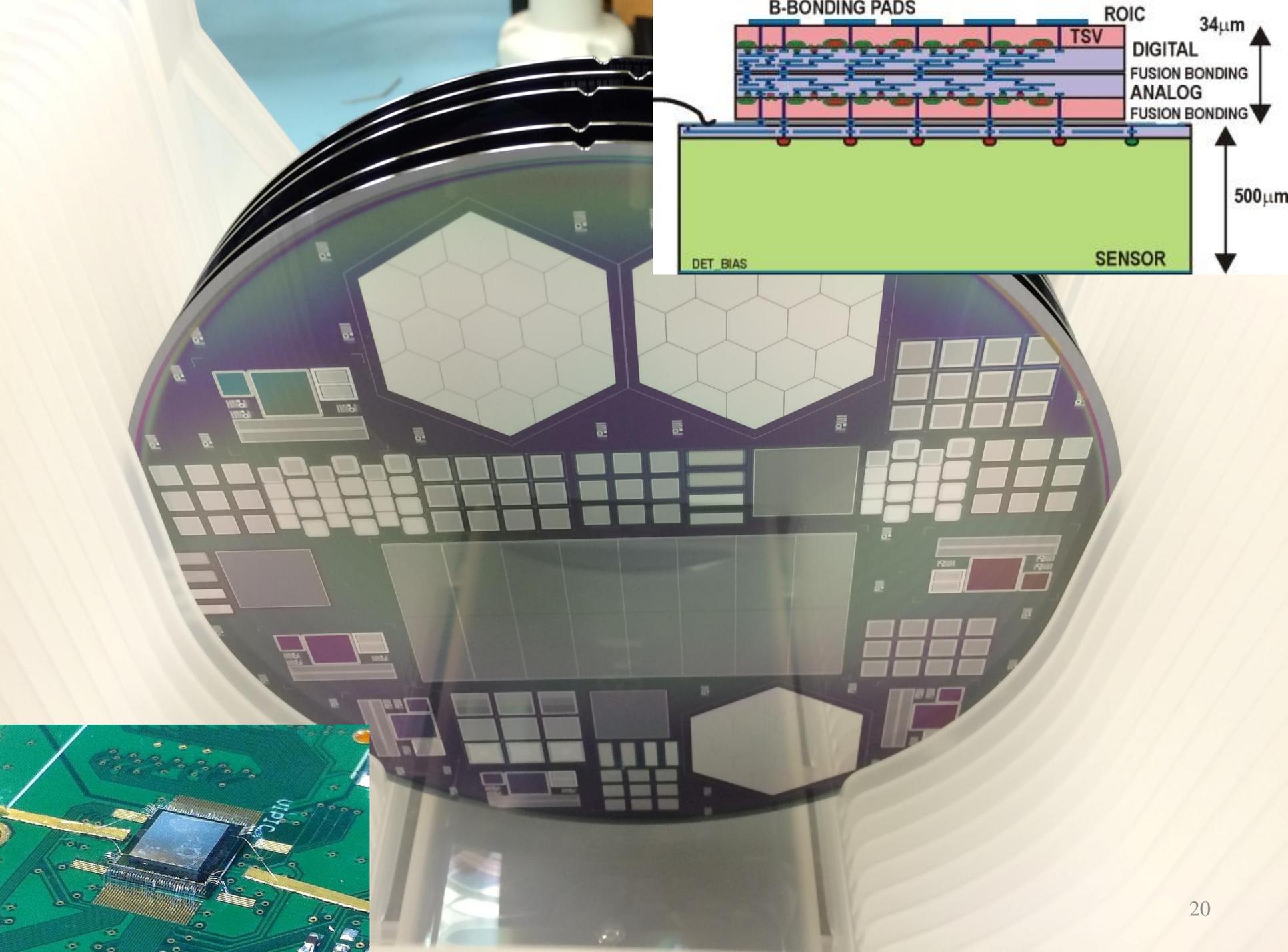


Mixed CMOS-3/5 100mm InP/CMOS

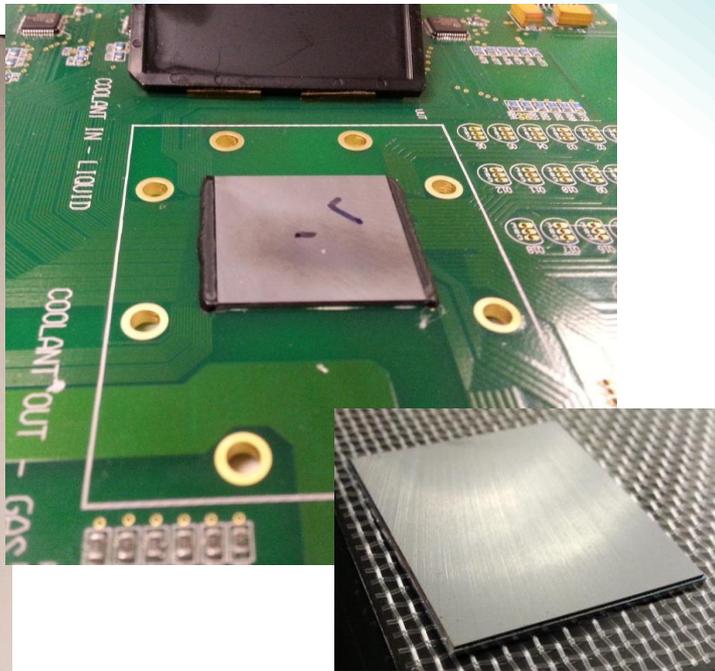
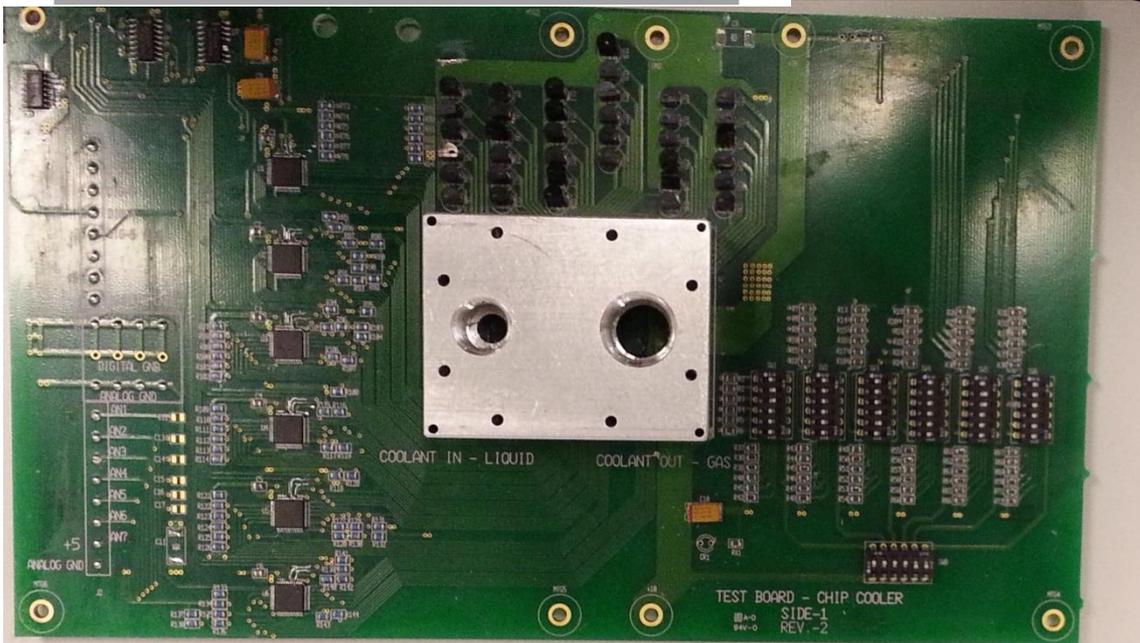
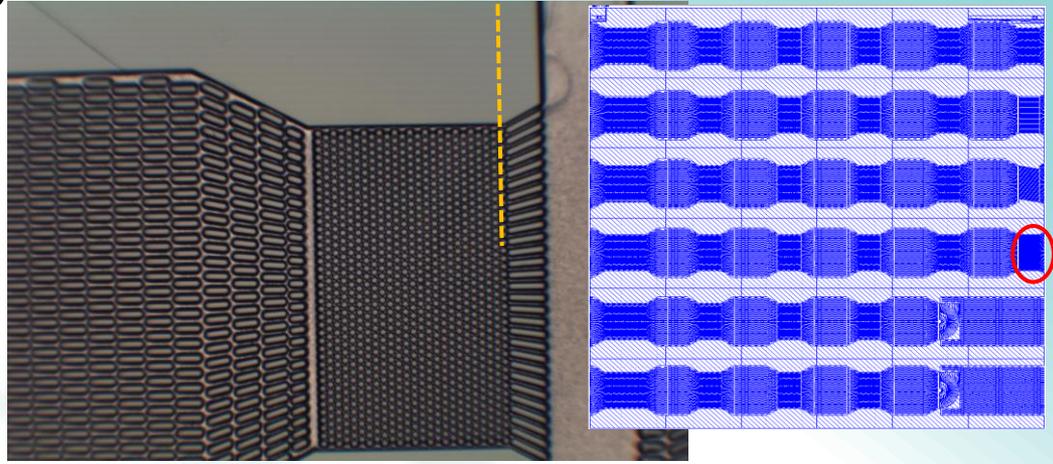
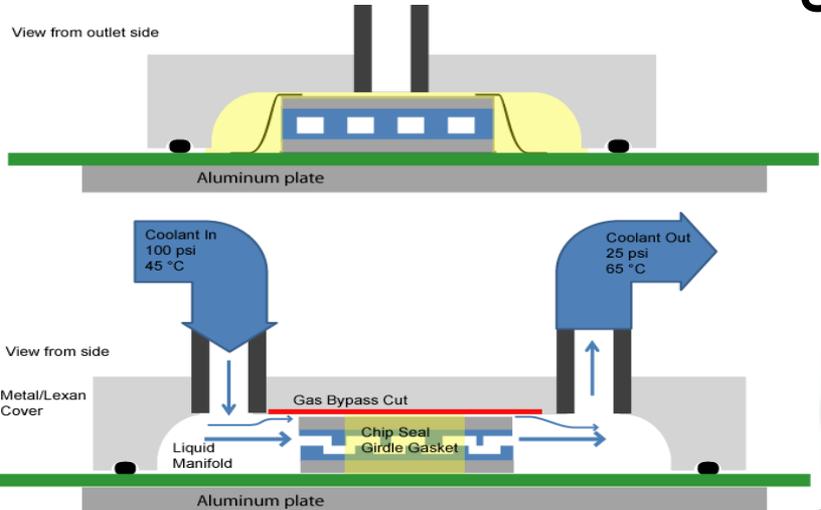


- GaN
- 3D CMOS/InP/GaN
- GaAs
- Graphene

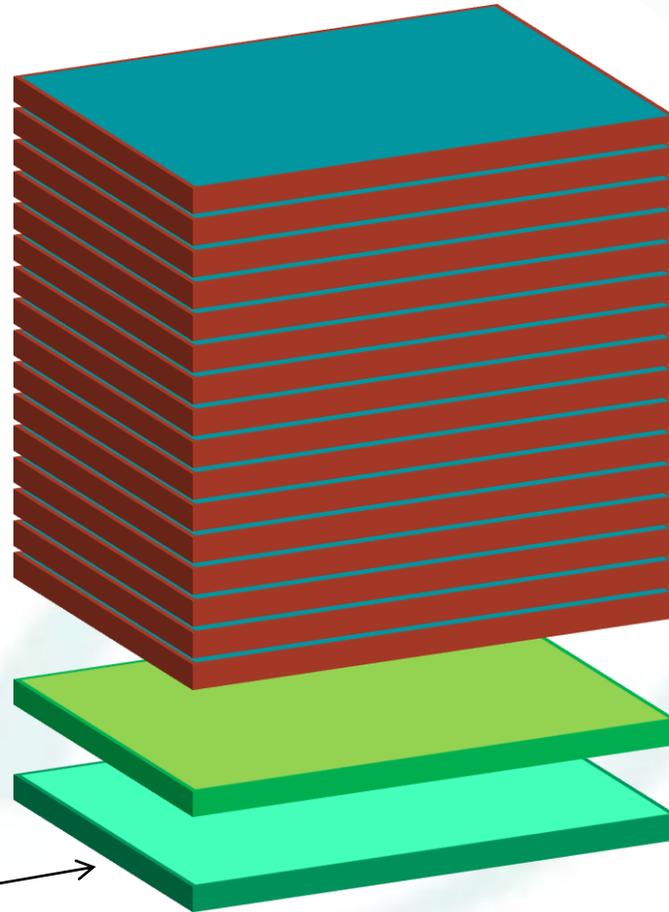
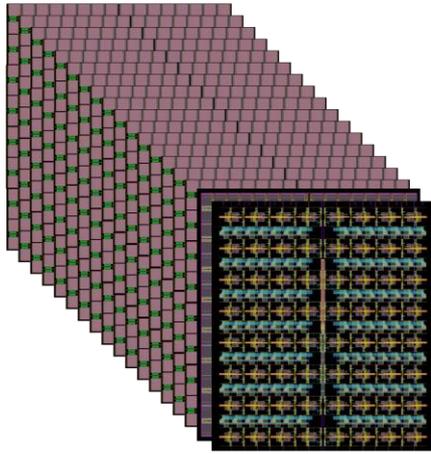




Advanced 3D Cooling



DiRAM4 “Dis-Integrated” 3D Memory



DRAM layers
4xnm node

2 million vertical
connections per lay per
die

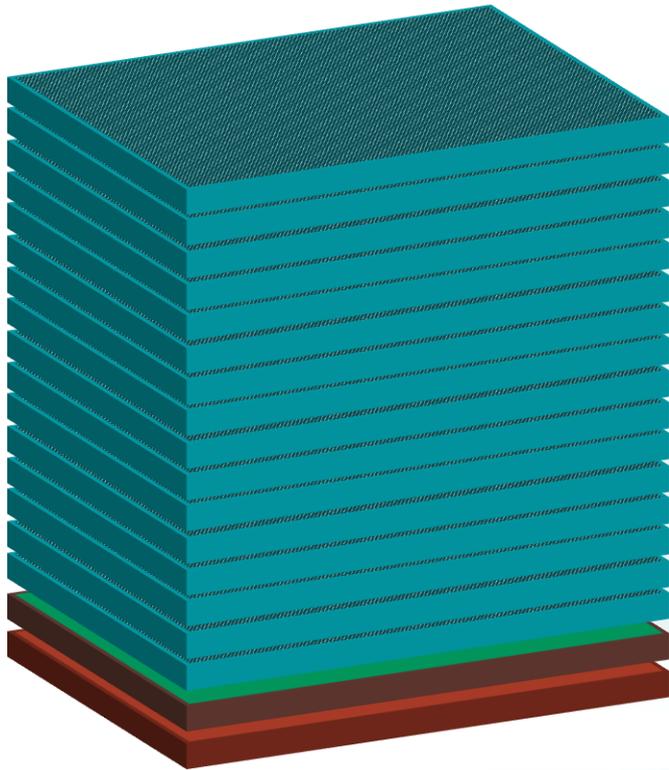
I/O layer contains: I/O,
interface logic and
R&R control CPU.

65nm node

Better yielding than 2D equivalent!

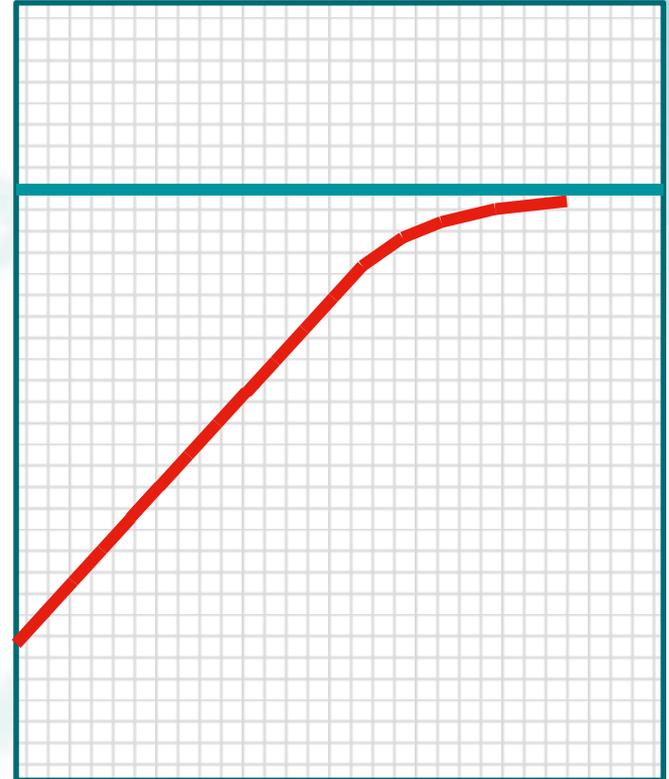
Controller layer
contains: sense amps,
CAMs, row/column
decodes and test
engines. 40nm node

Bi-STAR Repair Improves Yield



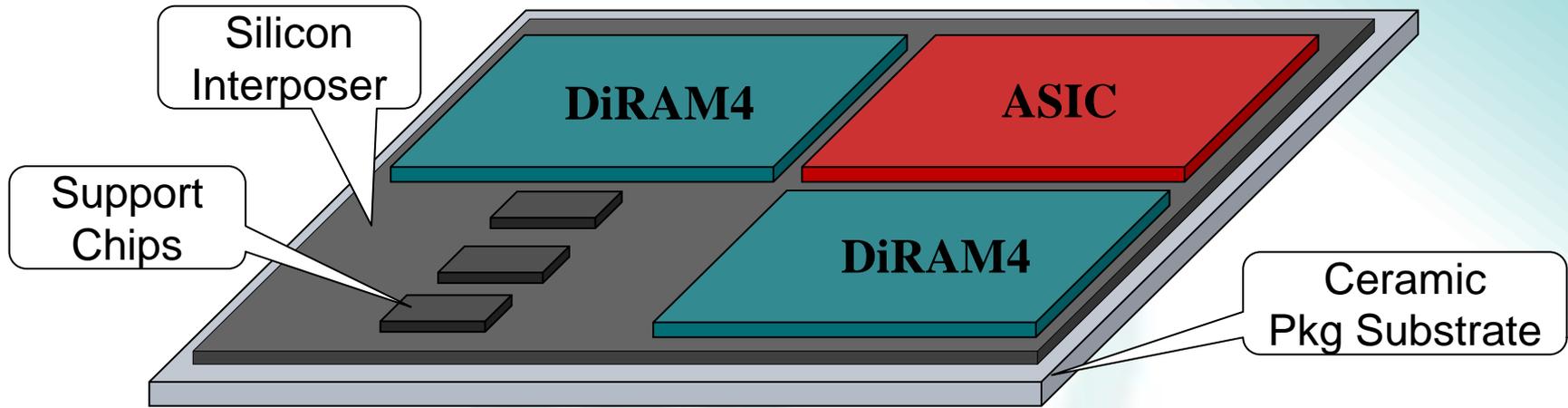
100%

Yield



Stack Height

HPC Processor Modules



Si Interposer-based Ceramic Package

e.g. DiRAM4 plus Custom Processor

50 μ - 100 μ pitch Copper Pillar Die-to-Interposer-to-Die Interconnect

~ 10000 Connections – Mostly die-to-die inside package

~250 μ pitch C4 Bump Interposer-to-Ceramic Package Substrate Interconnect

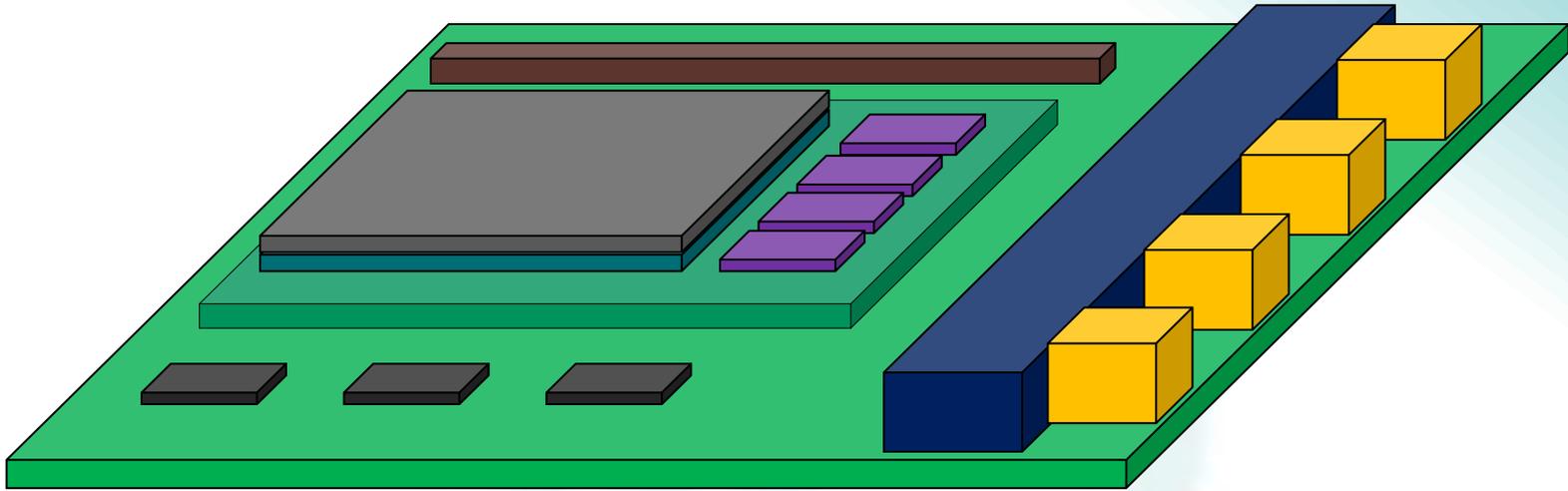
~ 2000 Connections – Lots of replicated power connections

1 mm pitch Solder Bump Package Substrate-to-Customer PCB Interconnect

Several Hundred of Connections

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And Full Subsystem Modules



Sub-system Modules

e.g. (Tezzaron / Luxtera Optical Memory Module)

*Multiple Packages and /or Die
on High Performance PCB with System Connectors
(Electrical: Card edge or Plugs, Optical: Fiber-optic Cable connectors)*



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2.5/3D CHANGE IS AT HAND

The Silent Revolution

Samsung

16Gb NAND flash (2Gx8 chips),
Wide Bus DRAM, VNAND

Micron
HMC DRAM

Intel

CPU + memory

Sony

CMOS Sensor

Xilinx

4 die 65nm interposer

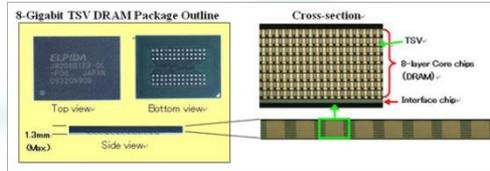
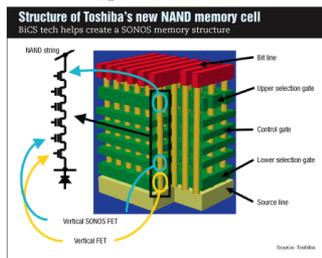
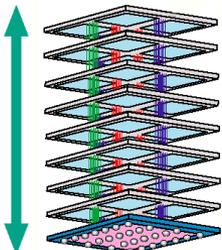
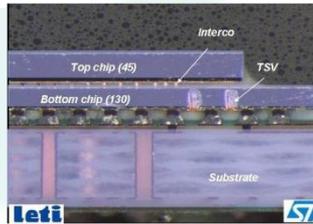
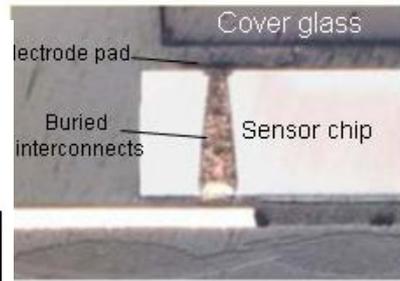
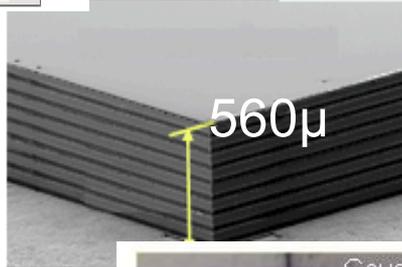
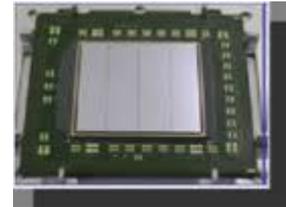
Raytheon/Ziptronix

PIN Detector Device

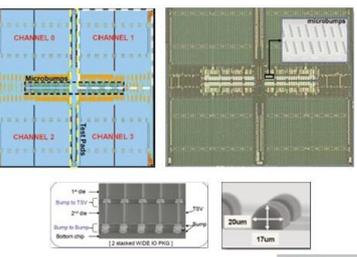
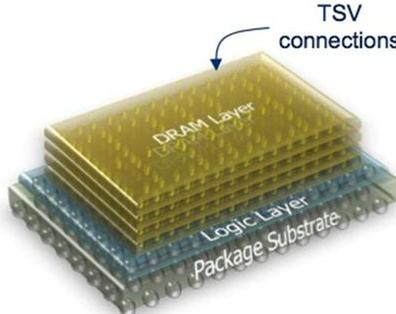
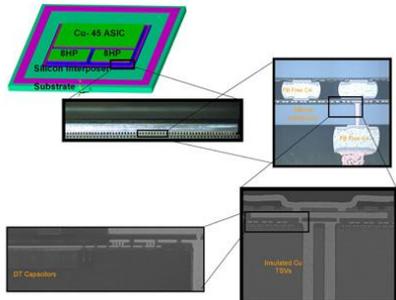
IBM

RF Silicon Circuit Board / TSV
Logic & Analog

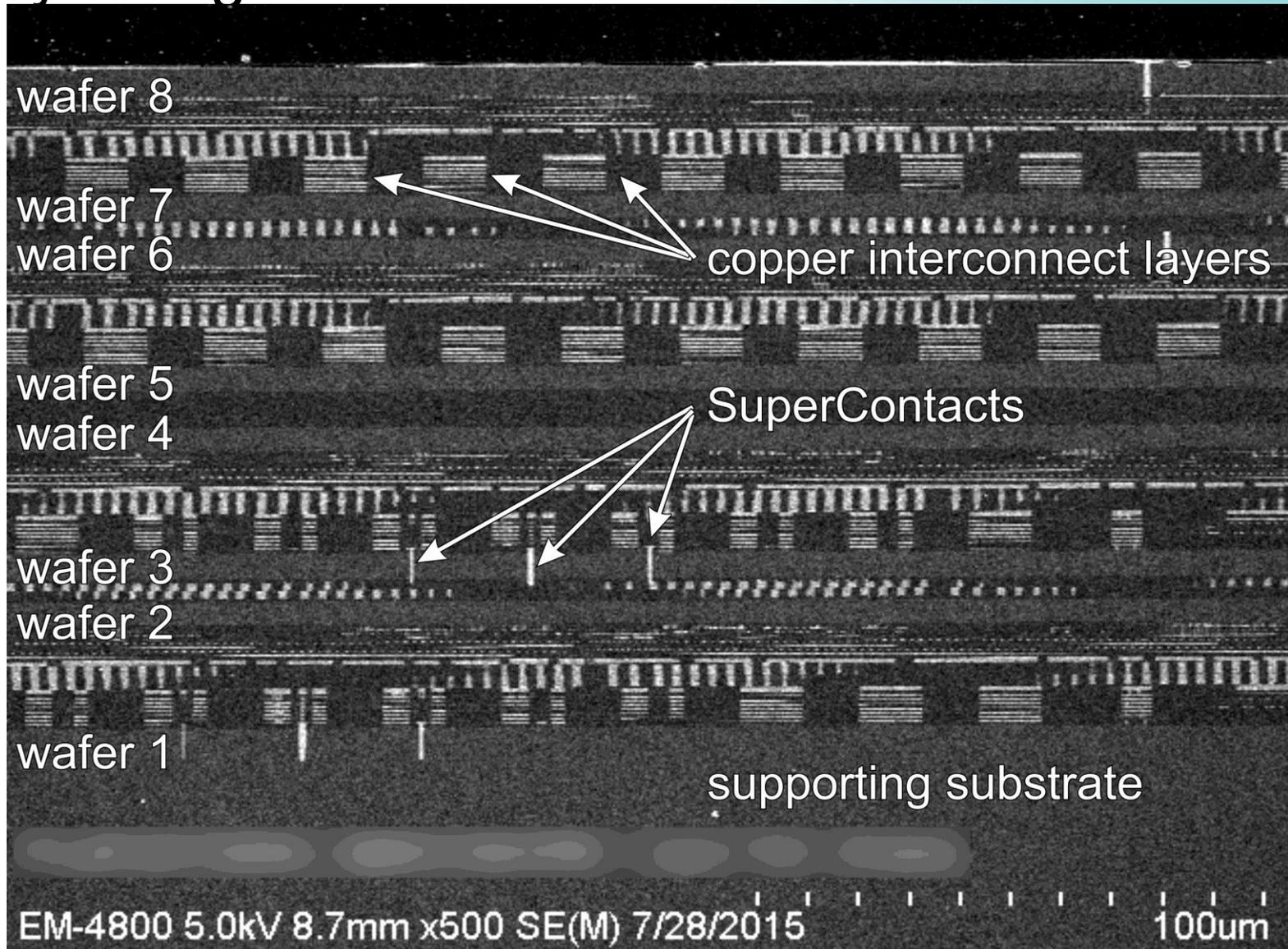
Toshiba
3D NAND



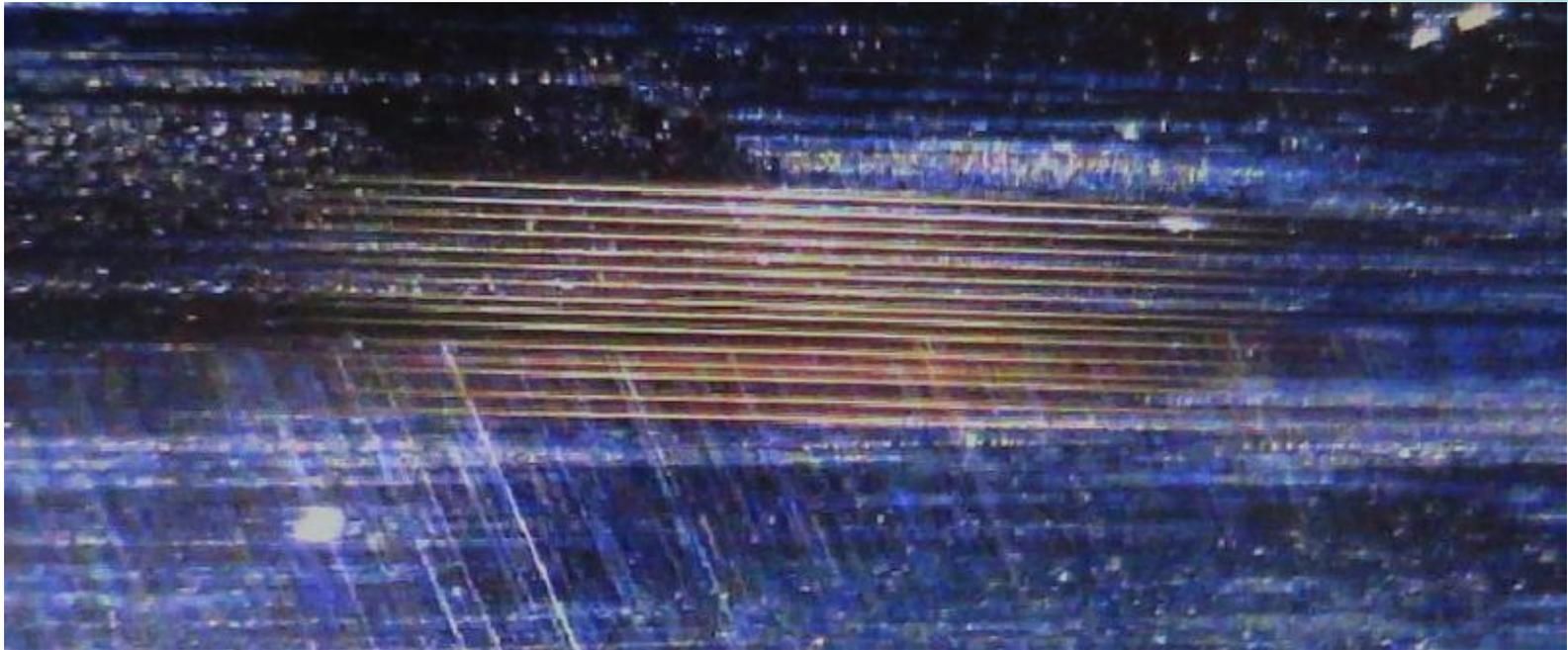
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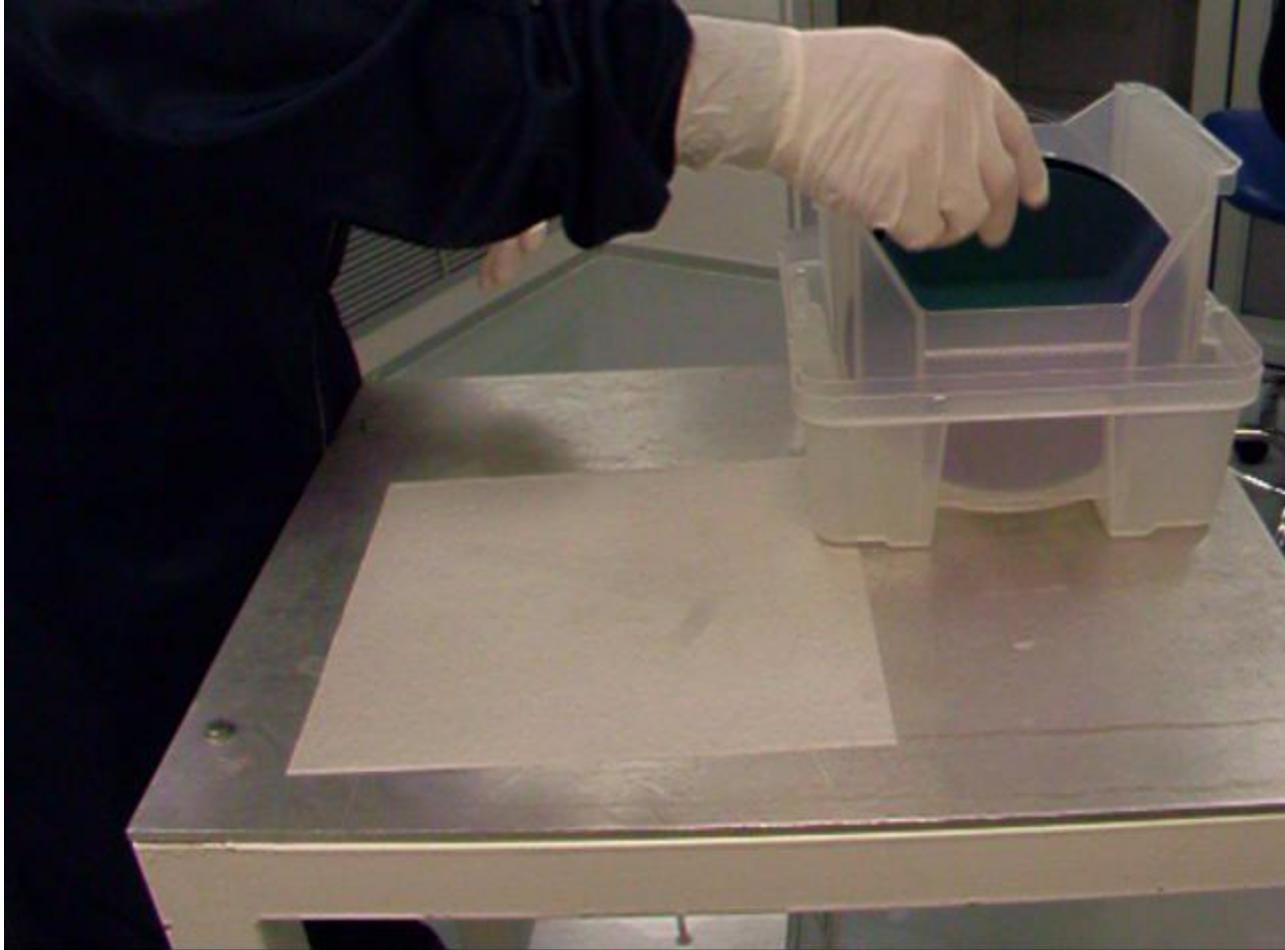
8 Layer Logic Stack



16 Layer Mechanical Device Stack

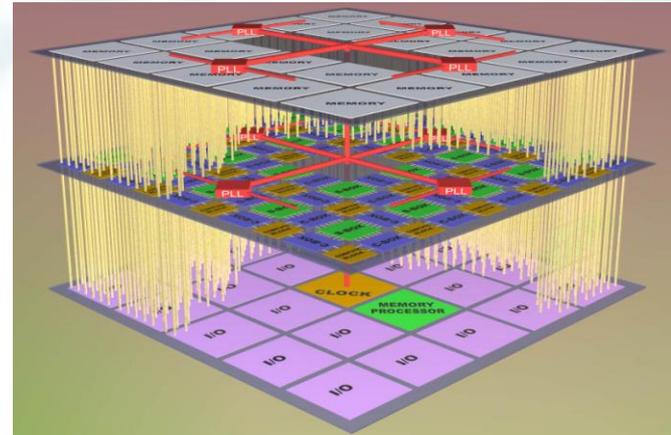


Bonding in Action



Summary

- 2.5/3D market is in the adoption cycle
 - Moving from novelty to mainstream
- Drivers are:
 - Heterogeneous integration
 - SWaP
 - Increasing performance
 - Lower system costs
- First markets are:
 - Logic – Memory
 - Sensors
- Significant industry shifts will happen
 - Silicon circuit cards with “Lego” blocks



Backup





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NOVATI OVERVIEW

Austin Facility Overview

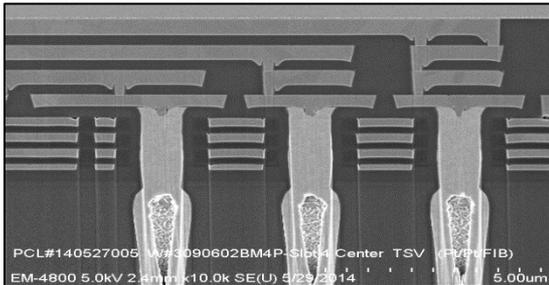
- 110 Employees: 90 in Ops and Engineering
- Over 150 production grade tools
- 68,000 sq ft Class 10 clean room
- 24/7 operations & maintenance
- Manufacturing Execution Systems (MES)
- IP secure environments, robust quality systems
- ISO certified/ITAR registered
- Full-flow 200mm silicon processing, 300mm back-end (Copper/Low-k)
- Process library with > 25000 recipes
- Novel materials (ALD, PZT, III-V, etc)
- Copper & Aluminum BEOL
- Contact through 193nm & IR lithography
- Silicon, SOI and Transparent MEMS substrates
- Electrical Characterization and Bench Test Lab
- Onsite analytical tools and labs: SIMS, SEM, TEM, Auger, VPD, ICP-MS, etc



Our Technology Platform

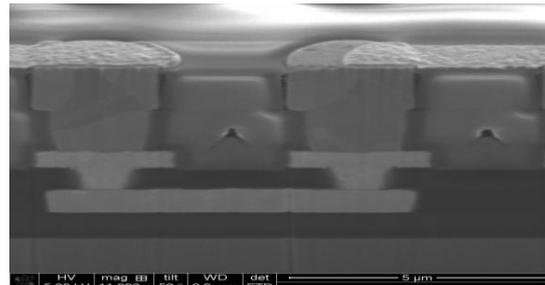


Focused on Convergence of Three Critical Areas



BEoL Split-Fab

- Copper BEoL to support multi-level metal, redistribution, TSV
- High-k capacitors, precision resistors, magnetics, waveguides



2.5D & 3D Integration

- Hybridization of Silicon and non-silicon (quartz, GaAs, InGaAs, GaN) substrates
- Interposers, die-to-wafer, wafer-to-wafer, TSV insertion

23 50.942 V VANADIUM	24 51.996 Cr CHROMIUM	25 54.938 Mn MANGANESE	26 55.845 Fe IRON	27 58.933 Co COBALT
41 92.906 Nb NIOBIUM	42 95.96 Mo MOLYBDENUM	43 (98) Tc TECHNETIUM	44 101.07 Ru RUTHENIUM	45 101.07 Rh RHODIUM
73 180.95 Ta TANTALUM	74 183.84 W TUNGSTEN	75 186.21 Re RHENIUM	76 190.23 Os OSMIUM	77 190.23 Ir IRIDIUM

Novel Materials

- More than 60 elements from periodic table can be leveraged in the fab today
- World's fastest most flexible on-boarding of new materials

**Enabling Advanced Processing, Smart Sensors, Advanced Imagers,
RF/Power Electronics**

